

**Amendments to the Specification:**

Please amend the specification as follows:

*Please replace the paragraph starting at page 4, line 26, with the following:*

The electrode may be a cathode, for example, a cylindrical target, which functions as a cathode. The advantage of a cylindrical target in the context of the present invention is that the contacting device may stand still, since the cylindrical target rotates. During rotation of the cylindrical target, the device may continuously or intermittently remove or add material to the target.

*Please replace the paragraph starting at page 5, line 27, with the following:*

In a first alternative the contact zone overlaps with the end zone, e.g. covers the end zone, e.g. is equal to the end zone. The end zone is the zone which is not sputtered. In a second alternative the contact zone overlaps with the zone of racetrack return, e.g. covers the zone of racetrack return, e.g. is the zone of racetrack return on the target. In a third alternative the contact zone overlaps the erosion zone, e.g. covers the erosion zone, e.g. is the erosion zone. The erosion zone is the zone of normal target consumption, also the zone of straight racetracks.

*Please replace the paragraph starting at page 6, line 4, with the following:*

Amongst others, the third alternative of the invention is particularly useful for materials that are sensitive to so-called 'nodule' formation. 'Nodules' are local irregularities that form on the surface of the target during deposition of the target material. The nodules differ in hardness or electrical conductivity from ~~form~~ their immediate surroundings thereby disturbing the uniformity of the sputtering process. The following materials are particularly known for their sensitivity to nodule formation:

- ITO - indium tin oxide - targets, or
- ZnAlO - zinc oxide ~~zineoxide~~ doped with ~~aluminium~~ aluminum
- TiN, Ti, CoTi, and Al.

The method is most suited for ITO targets.